CLAIM AMENDMENTS:

1-7. (canceled)

8. (currently amended) An ultra-narrow band fluorine laser apparatus comprising a laser chamber which is filled with a laser gas including fluorine and to which a predetermined discharge voltage is applied between a cathode and an anode thereof for causing a fluorine laser to oscillate laser light to be supplied as an exposure light source of an exposure apparatus, wherein ~~total pressure of said laser gas is set equal to or lower than 2.8 atm such that~~ the ultra-narrow band fluorine laser apparatus is operated to narrow a bandwidth of laser light oscillated by said laser chamber ~~is narrowed~~ to a desired value by maintaining total pressure of said laser gas equal to or lower than 2.8 atm.

9. (currently amended) An ultra-narrow band fluorine laser apparatus comprising a laser chamber which is filled with a laser gas including fluorine and to which a predetermined discharge voltage is applied between a cathode and an anode thereof for causing a fluorine laser to oscillate laser light to be supplied as an exposure light source of an exposure apparatus, wherein ~~total pressure of said laser gas is set equal to or lower than 2.8 atm such that~~ the ultra-narrow band fluorine laser apparatus is operated to narrow a bandwidth of laser light oscillated by said laser chamber ~~is narrowed~~ to a

desired value without use of an optical element for further narrowing said bandwidth of laser light by maintaining total pressure of said laser gas equal to or lower than 2.8 atm.

10. (currently amended) The ultra-narrow band fluorine laser apparatus according to claim 9, wherein said total pressure of said laser gas is ~~set~~ maintained equal to or lower than 1 atm and the bandwidth is narrowed to a desired value not exceeding 0.6 pm.

11. (currently amended) The ultra-narrow band fluorine laser apparatus according to claim 8, wherein the interval between the cathode and anode is set at a predetermined length to maintain glow discharge without causing dielectric breakdown between said cathode and anode when total pressure of said laser gas is ~~set~~ maintained equal to or lower than 2.8 atm.

12. (currently amended) The ultra-narrow band fluorine laser apparatus according to claim ~~12~~ 8, wherein a discharge mode for causing said glow discharge is longitudinal discharge in which discharge occurs in the same direction as an optical axis of laser light oscillated in said laser chamber.

13. (previously presented) The ultra-narrow band fluorine laser apparatus according to claim 8, further comprising an oscillator including said

laser chamber and an amplifier for amplifying power of laser light oscillated by the oscillator and supplying it as an exposure light source for said exposure apparatus.

14. (previously presented) The ultra-narrow band fluorine laser apparatus according to claim 13, wherein a discharging mode of the glow discharge caused between the cathode and anode in said laser chamber is transverse discharge in which discharge occurs in a direction perpendicular to an optical axis of laser light oscillated in said laser chamber and wherein the transverse discharge decreases the discharge voltage applied between said cathode and anode to a desired voltage such that glow discharge is maintained without causing dielectric breakdown between the cathode and anode.

15. (new) The ultra-narrow band fluorine laser apparatus according to claim 8, wherein the ultra-narrow band fluorine laser apparatus is operated to narrow the bandwidth of laser light to about 0.2 to 0.3 pm.

16. (new) The ultra-narrow band fluorine laser apparatus according to claim 9, wherein the ultra-narrow band fluorine laser apparatus is operated to narrow the bandwidth of laser light to about 0.2 to 0.3 pm.